ABSTRACT

A low emissivity film which comprises:

a substrate; and

a coating of oxide and metallic films alternately formed on the substrate in a total of (2n+1) layers where n is an integer being equal to or more than 1, with an innermost layer thereof being an oxide film,

wherein the oxide film (B) formed on the outer side of the metallic film (A) being most apart from the substrate, is a single layer film or a multi-layer film having at least a film whose major component is hexagonal zinc oxide; and

a value of a diffraction angle 2θ (center of gravity position) of (002) diffraction line of the hexagonal zinc oxide of the low emissivity film in X-ray diffraction method using CuKα radiation, is not smaller than 33.88° and not larger than 35.00°.

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